

Special Issue

Research Progress in Dust Control Technology

Message from the Guest Editors

This Special Issue aims to publish state-of-the-art technologies for dust control across various production and operational settings. The scope covers typical dust sources, including mining, tunnel construction, metal and powder processing, thermal power plants, cement plants, and waste incineration. Research topics encompass the optimization and enhancement of conventional dust control technologies (such as spraying, ventilation, dust collectors, foam suppression, and chemical suppressants), the application of emerging technologies and materials (including nano-coating, electrostatic and pulsed spraying, and bio-based suppression), digitalization and intelligent control (such as the Internet of Things, artificial intelligence, and digital twins), and the development of integrated dust control systems.

Guest Editors

Dr. Jianguo Liu
Prof. Dr. Shihang Li
Dr. Chaohang Xu

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Processes
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
processes@mdpi.com

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Editor-in-Chief

Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

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